

Atty Docket No.: 2000-0484B/N1085-90119

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE****In Re Patent Application of:**  
**Cheng et al.****Group Art Unit: 1765****Application No.: 10/649,472****Examiner: Chen, Kin Chan****Filing Date: August 27, 2003****For: Novel Chemical-Mechanical Polishing  
CMP Process for Shallow Trench Isolation****Date: January 9, 2006****Mail Stop AF  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450****RECEIVED  
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JAN 09 2006***Do not enter**fcc 1/7/06***AMENDMENT AFTER FINAL****Sir:**

This paper is responsive to the Office Action dated September 13, 2005. A petition for a one (1) month extension of time to extend the response due date to January 13, 2006 is included herewith. Kindly enter the following amendments:

**Amendments to the Specification** begin on page 2 of this paper.

**Amendments to the Claims** are reflected in the listing of claims which begins on page 3 of this paper.

**Remarks** begin on page 6 of this paper.